

Application No.: 10/692,588

Docket No.: JCLA10198

In The Claims:

Claim 1. (currently amended) An evaporation method, comprising:

providing a substrate, wherein the substrate is rotating along an axis at fixing the center of the substrate and perpendicular to the plane of the substrate rotating the substrate;

defining a circular trace by using the center of the substrate as the center of the circular trace;

providing a heater right under a point on the circular trace, wherein there is a line on the plane of the substrate as a tangent to the point on the circular trace;

providing a source supplying device, wherein the source supplying device supplies an evaporation source to the heater along a supplying direction and there is a vector from the source supplying device to the heater along the supplying direction;

~~disposing the heater and the source supplying device under a point of the circular trace and adjusting the supplying direction of the source supplying device for paralleling so that a projection of the vector on the plane of the substrate is parallel to the line the supplying direction and a tangential direction of the point of the circular trace; and~~

heating the evaporation source by the heater for evaporation.

Claim 2. (original) The evaporation method of claim 1, further comprising disposing a shelter between the source supplying device and the substrate for defining an evaporation region.

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Claim 3. (original) The evaporation method of claim 2, wherein a radius of the evaporation region is substantially similar to that of the circular trace.

Claim 4. (original) The evaporation method of claim 1, wherein a rotational direction of the substrate is clockwise.

Claim 5. (original) The evaporation method of claim 1, wherein a rotational direction of the substrate is counterclockwise.

Claim 6. (original) The evaporation method of claim 1, wherein the evaporation source is aluminum or silver.

Claim 7. (currently amended) An evaporation apparatus for depositing a film on a substrate, the evaporation apparatus comprising:

a rotator ~~fixing the center of a substrate~~ driving the substrate to be rotating along an axis at the center of the substrate and ~~rotating the substrate~~ to define a circular trace;

a heater, disposed right under a point of on the circular trace, wherein there is a line on the plane of the substrate as a tangent to the point on the circular trace; and

a source supplying device, disposed over the heater, wherein the source supplying device supplies an evaporation source to the heater along a supplying direction and there is a vector from the source supplying device to the heater along the supplying direction and a projection of

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the vector on the plane of the substrate is parallel to the line ~~is parallel to a tangential direction of the circular trace.~~

Claim 8. (currently amended) The evaporation apparatus of claim 7, further comprising a shelter disposed between the source supplying device and the substrate for defining the an evaporation region, wherein the shelter has an opening for defining the evaporation region on the substrate.

Claim 9. (original) The evaporation apparatus of claim 8, wherein the opening is a circular opening.

Claim 10. (original) The evaporation apparatus of claim 9, wherein a radius of the evaporation region is substantially similar to that of the circular trace.

Claim 11. (original) The evaporation apparatus of claim 7, wherein the evaporation source is aluminum or silver.

Claim 12. (original) The evaporation apparatus of claim 7, wherein a rotational direction of the substrate is clockwise.

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Claim 13. (original) The evaporation apparatus of claim 7, wherein a rotational direction of the substrate is counterclockwise.

Claim 14. (original) The evaporation apparatus of claim 7, wherein the heater is a rectangular loading crucible.